



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Inventor Li et al.
Assignee Micron Technology, Inc.
Group Art Unit 2822
Examiner Toniae M. Thomas
Attorney's Docket No. MI22-1398
Customer No. 021567
Title: Low k Interlevel Dielectric Layer Fabrication Methods

PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING

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Wells St. John P.S.
601 West First Avenue, Suite 1300
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REMARKS

This Request for Continued Examination is submitted in an abundance of caution simply to place certain references before the Examiner for consideration. The references are referred to in the Information Disclosure Statement presented herewith.

No new matter is being presented in this application.